

# Welcome to the 1985 MRS Fall Meeting



This year MRS sees two Fall Meetings.

In Strasbourg, France, the European Materials Research Society Fall Meeting runs from November 26 through 29 and focuses on Advanced Materials R & D for Transport. Three symposia treating particular materials issues in the transportation industry will be held in the beautiful Council of Europe facility. To those of you finding this issue of the **BULLETIN** in your registration material in Strasbourg, welcome to the first Fall Meeting of the European MRS. You are participating in a forum specifically designed to enhance communication among materials researchers whose necessarily interdisciplinary approach requires such topically focused symposia. The symposia chairpersons and the local staff have invested a large effort in planning the program and logistics of your meeting, and we are sure you will find this meeting most productive. We would also welcome your continued participation in the activities of E-MRS. You may obtain more information about the Society by contacting the headquarters at the Strasbourg address given in the front of this **BULLETIN**.

In Boston, the annual Fall Meeting convenes December 2 and runs through December 7. On behalf of the Materials Research Society, let me welcome participants arriving in Boston. Normally in describing our ever expanding meeting activities, strings of superlatives are necessary. This 1985 Fall Meeting is certainly no exception. As you see from your program, we have 20 topical symposia covering research at the forefront of their respective fields. We have the ever popular luncheon Symposium X which offers the nonspecialist insight into advances in various materials areas. And, completing the list, we have a wholly new departure for MRS in Symposium Y, which delves into the issues of materials education, a field which is clearly the precursor to the pursuit of all the work reported in our forums.

Taken together this program is the largest yet offered to MRS participants and comprises over 1,250 individual presentations. This is the first year we find MRS activities

running in two hotels and are fortunate to have been able to take advantage of the Boston Marriott/Copley Place and the Westin Hotel which are so convenient to each other.

A great deal of planning is required to bring together a meeting such as this. First and foremost among those who have devoted their time and expertise to this task are the meeting chairs. These are John Baglin of IBM, David Biegelsen of Xerox, and John Fan of the MIT Lincoln Laboratory. The high quality of the program and its coordination can be attributed to the long hours invested by such talented individuals as these and we certainly owe them a debt of gratitude. Each symposium has likewise benefited from the technical excellence and diligence of their respective chairs. These scientists have formulated outstanding programs which will represent the latest, most incisive, advances in their fields by and to their broad interdisciplinary international groups of participants.

Once again the central objective of MRS for its meetings has been superbly fulfilled. Behind the scenes, much of the logistical support for this largest-ever meeting has been provided by the MRS Headquarters staff under the direction of Executive Director John Ballance. With the MRS Headquarters just entering its third year of existence, it has managed this gargantuan task with great success.

In addition to the technical symposia, you will find that this year's Fall Meeting offers a substantially expanded program of short courses. The 14 courses, available on Friday and Saturday of the meeting, were assembled by L. Ralph Dawson, cochair of the MRS Education Committee. Also expanded this year is the MRS Equipment Show run for MRS by the American Institute of Physics. Over 100 booths will display the "implements of our profession" and I encourage all participants to visit the show which is open Tuesday through Thursday. Those attendees who are interested in employment opportunities may take advantage of the MRS Job Placement Center. The Center, which was well utilized the first time it was offered last year, will again be handled for MRS by the AIP Placement

Service.

Let me also invite each participant to attend the Awards Ceremony on Monday, December 2. At that time we will have the distinct privilege of presenting 15 graduate student awards for outstanding papers presented at this meeting and to present the Von Hippel Award to John W. Cahn of NBS. Please join me in honoring our award recipients and in attending the reception which follows.

Beyond the events of the annual Fall Meeting, many more exciting MRS activities have taken place. The Education Committee has implemented the travel grant and speaker tour programs for Student Chapters. New local Sections and Student Chapters are forming, some of which will be chartered at the All-Society Plenary Session on Wednesday, December 4. The first MRS produced proceedings volumes rolled off the presses in 1985. You will find many of these displayed in the meeting registration area. And, *Journal of Materials Research*, the new MRS-owned, AIP published, comprehensive archival journal for our field, has been launched. Since this time last year, the number of full-time Headquarters staff has more than doubled, increasing from three to seven, in order to manage these expanded and new endeavors.

Going largely unnoticed, aside from the occasional note in the **BULLETIN**, is the year-round work of the 11 MRS committees. Much of the activity described above is initiated and overseen by these committees. Their function is vital to the health and vitality of the Society. During the Fall Meeting, the committees meet to formulate plans for the future and assess ongoing programs. These are individual MRS members contributing their talents to the Society's needs. I encourage any and all of you who would like to become involved in MRS and its future to express that interest to any official of MRS during or after the meeting.

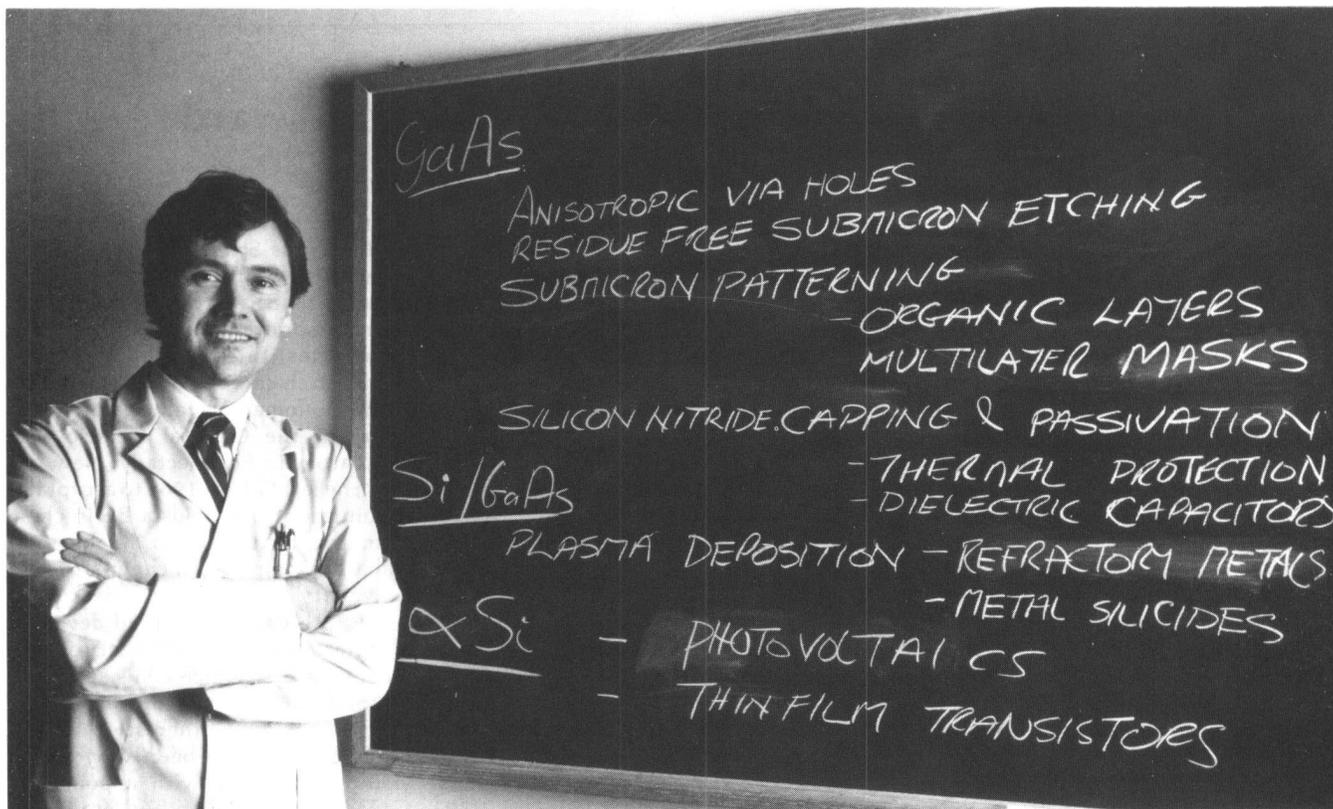
In closing, let me wish you, our participants, whether in Boston or Strasbourg, a very productive and stimulating week and an enjoyable stay in our host city.

Elton N. Kaufmann  
MRS President

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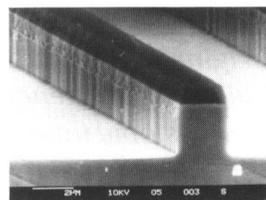
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\*Photo courtesy of SERC Central Facility for 3-5 semiconductors University of Sheffield UK.